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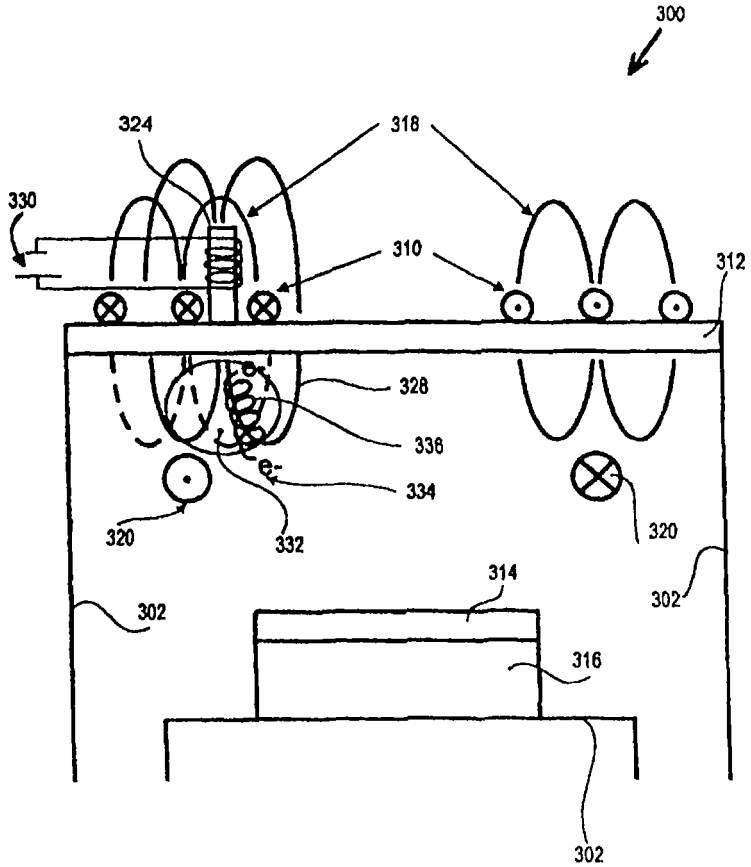
(54) Title: METHOD FOR IGNITING A PLASMA INSIDE A PLASMA PROCESSING REACTOR

(57) Abstract

The invention relates to a plasma processing reactor for processing a substrate. The plasma processing reactor includes a process chamber. The plasma processing reactor further includes an inductive coil configured to be coupled to a RF power source having a RF frequency wherein the inductive coil generates an electric field inside of the process chamber. The plasma processing reactor additionally includes a magnetic field producing device configured to produce a magnetic field inside the process chamber in proximity of the electric field.